


Claims

- [c1]  A thick film heater comprising
a target object to be heated, wherein said target object is located in an
environment of ambient temperatures significantly below 0 ° C;
a heating element consisting of an electrically thick film resistive
circuit applied directly to a surface of said target object; and
wherein said electrically thick film resistive circuit is polymer based.
- [c2] The thick film heater of claim 1 wherein said target object is designed to
operate at temperatures below -75 ° C.
- [c3] The thick film heater of claim 2 wherein said target object is designed to
operate at temperatures below -150 ° C.
- [c4] The thick film heater of claim 1 wherein said heating element is capable of
heat flux at least as great as 200 watts per square inch.
- [c5] The thick film heater of claim 1 wherein said target object is non-ferrous.
- [c6] The thick film heater of claim 5 wherein said target object is aluminum.
- [c7] The thick film heater of claim 5 wherein said target object is copper.
- [c8] The thick film heater of claim 5 wherein said target object is ceramic.
- [c9] The thick film heater of claim 1 wherein said target object is a high-
expansion steel.
- [c10] The thick film heater of claim 1 wherein said heating element further
comprises a dielectric layer disposed between said target object and said
electrically resistive circuit.
- [c11] The thick film heater of claim 10 wherein said heating element further
comprises a second dielectric layer disposed over said electrically resistive
circuit, away from said target object.
- [c12] The thick film heater of claim 10 wherein said dielectric layer consists of a

metal oxide .

- [c13] The thick film heater of claim 12 wherein said metal oxide is selected from the group consisting of TiO₂, SiO₂, and Al₂O₃.
- [c14] A method of manufacturing a thick film heater comprising a heating element applied directly to a surface of a target object, the method comprising the steps of:
- applying the heating element, comprising a thick film resistive circuit directly to the surface of the target object, wherein the thick film resistive circuit is made of a polymer-based ink;
 - curing the heating element at a temperature in excess of 150 ° C for a period of time in excess of thirty minutes; and
 - sealing the heating element with a dielectric layer.
- [c15] The method of claim 14 further comprising a plurality of said curing steps, wherein at least one of said curing steps occurs at a temperature in excess of 150 ° C for a period of time in excess of thirty minutes.
- [c16] The method of claim 14 further comprising the step of preparing the surface of the target object with a lower dielectric layer, and wherein the heating element in said applying layer is applied over the lower dielectric layer.
- [c17] The method of claim 14 wherein said curing step occurs at a temperature of 200 ° C or greater.
- [c18] The method of claim 14 wherein said curing step occurs for a period of two hours or longer.
- [c19] The method of claim 14 wherein the heating element is designed to operate at greater than 15 W/cm² .
- [c20] The method of claim 14 wherein the target object is non-ferrous.
- [c21] The method of claim 20 wherein the target object is aluminum.
- [c22] The method of claim 19 wherein the target object is copper.

- [c23] The method of claim 20 wherein the target object is ceramic.
- [c24] The method of claim 13 wherein the target object is high-expansion steel.
- [c25] The method of claim 13 wherein the polymer base of the thick film resistive circuit is an epoxy.
- [c26] The method of claim 24 wherein the polymer-based ink contains silver particles.

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